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**(54) HIGH PURITY SILICA GLASS FOR FAR ULTRAVIOLET AND ITS PRODUCTION**

(57)Abstract:

**PROBLEM TO BE SOLVED:** To produce silica glass having high far UV transmissivity and far UV resistance.

**SOLUTION:** This silica glass has 500-1,000° C set virtual temp.,  $\leq 5 \times 10^{16}/\text{cm}^3$  concn. of oxygen deficiency type defects and  $\leq 5 \times 10^{16}/\text{cm}^3$  concn. of oxygen excess type defects. It is produced by subjecting transparent silica glass formed using a high purity silicon compd. to virtual temp. setting treatment at 500-1,000° C for 100-2,000hr.

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